

FIG. 1

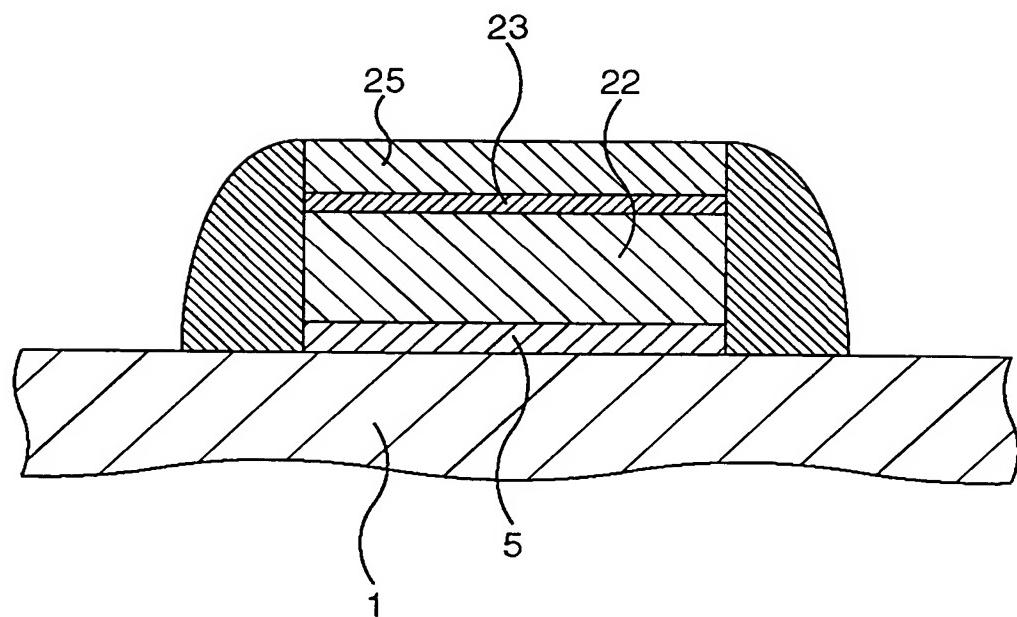


FIG. 2A

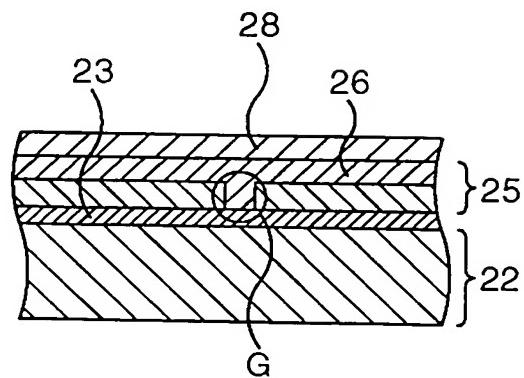


FIG. 2B

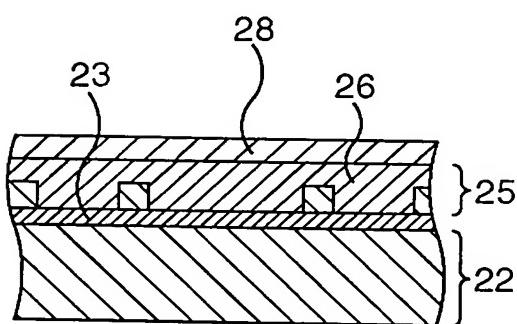


FIG. 2C

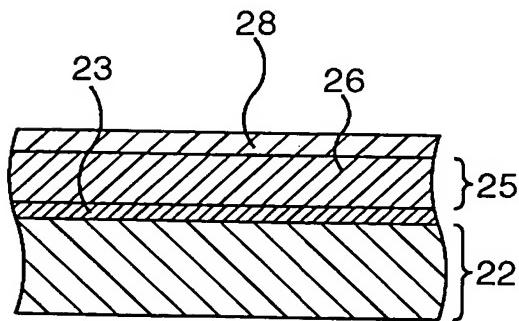
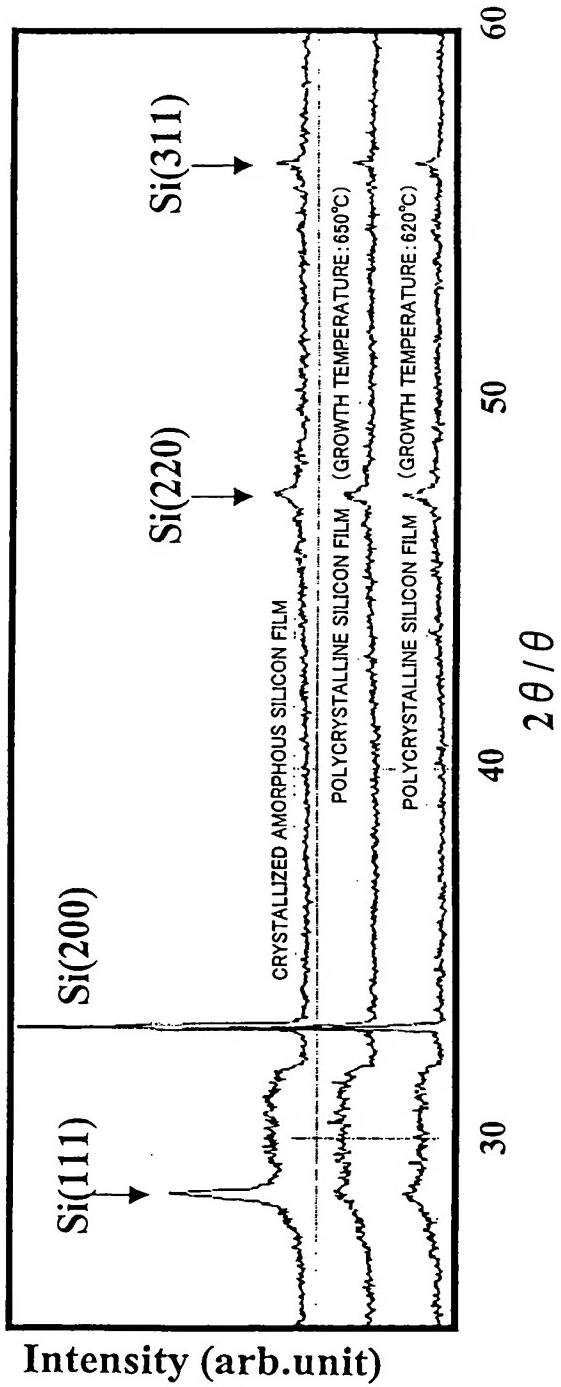


FIG. 3A



<X-RAY DIFFRACTION RESULTS OF VARIOUS SILICON FILMS>

FIG. 3B

BASE SILICON FILM	SILICIDE RESISTANCE VALUE
POLYCRYSTALLINE SILICON FILM	7. 2 (Ω/sq)
AMORPHOUS SILICON FILM	6. 4 (Ω/sq)
WITH CRYSTALLIZATION	5. 7 (Ω/sq)

<RESISTANCES OF CoSi₂ FOMED ON VARIOUS SILICON FILMS>

FIG. 4

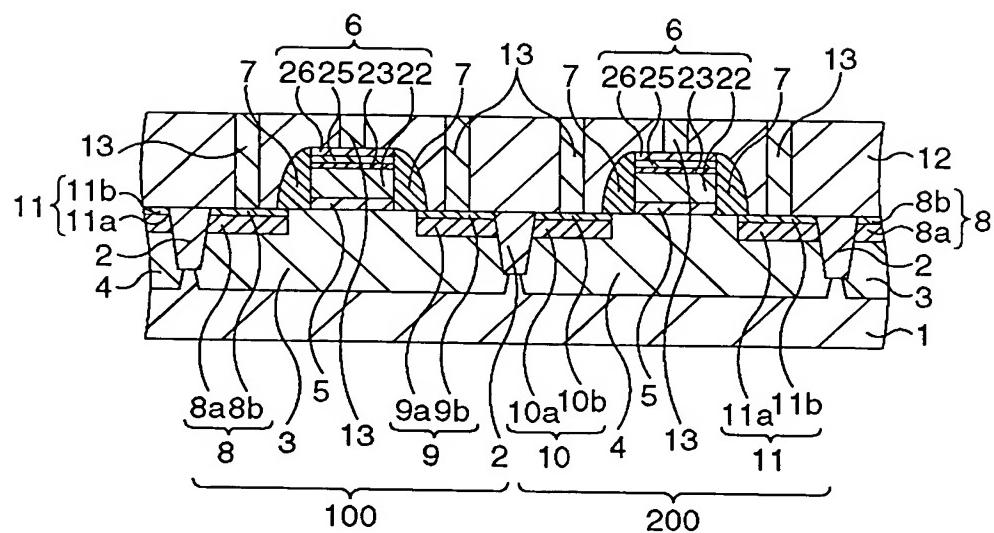


FIG. 5A

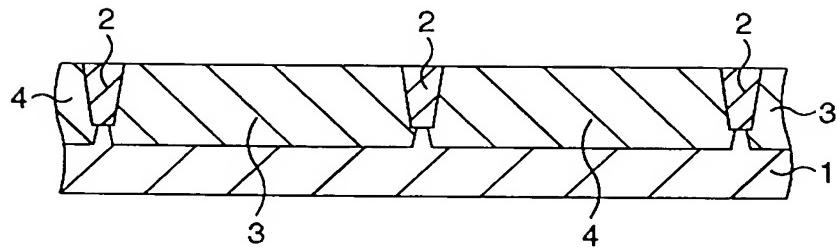


FIG. 5B

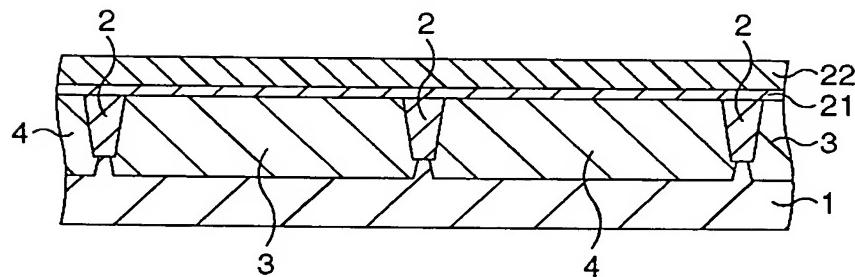


FIG. 5C

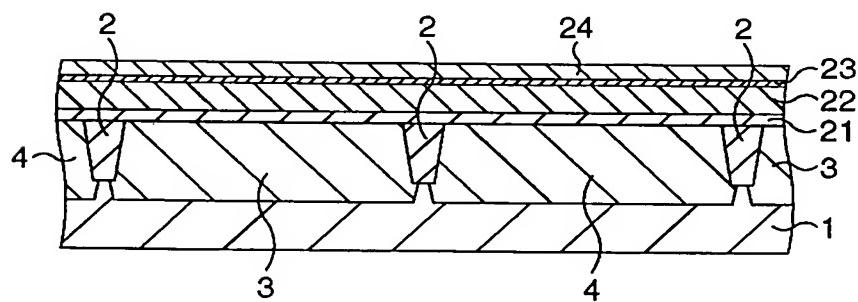


FIG. 5D

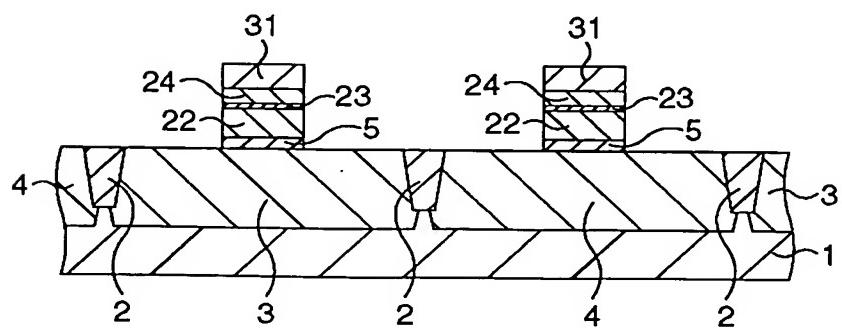


FIG. 6A

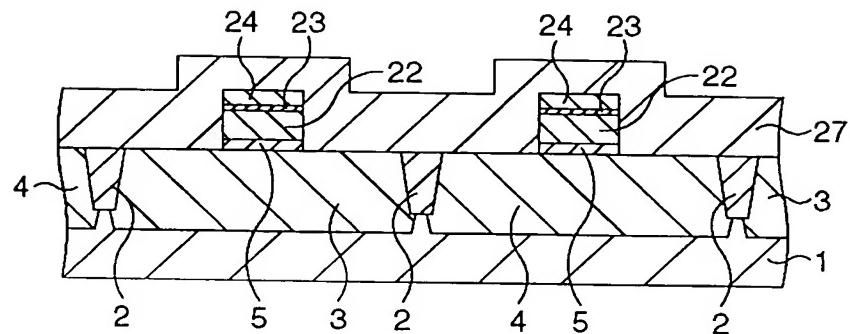


FIG. 6B

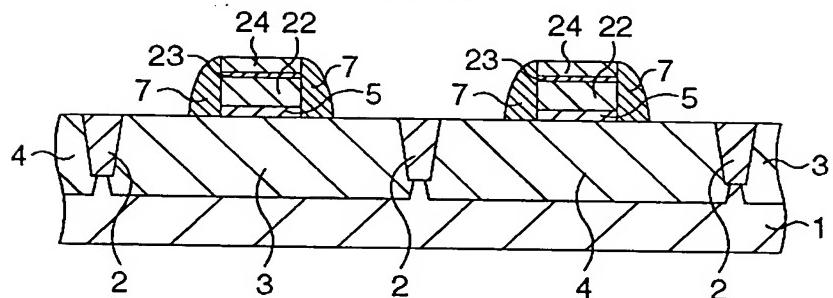


FIG. 6C

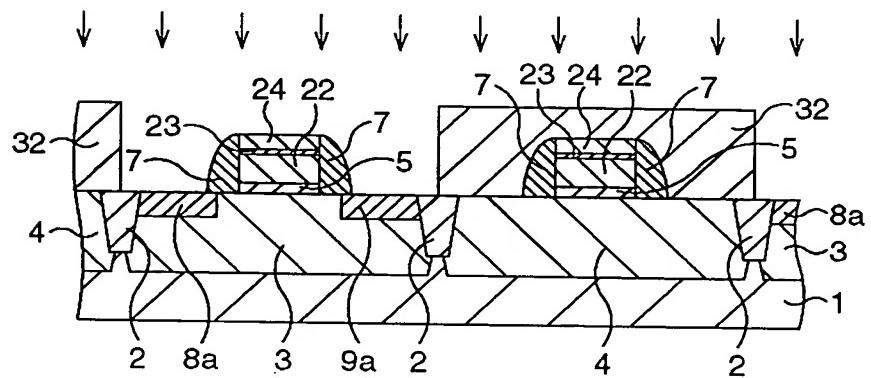


FIG. 6D

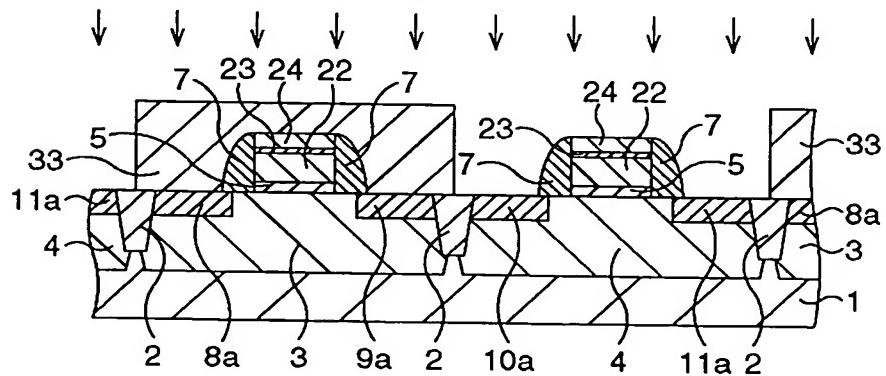


FIG. 7A

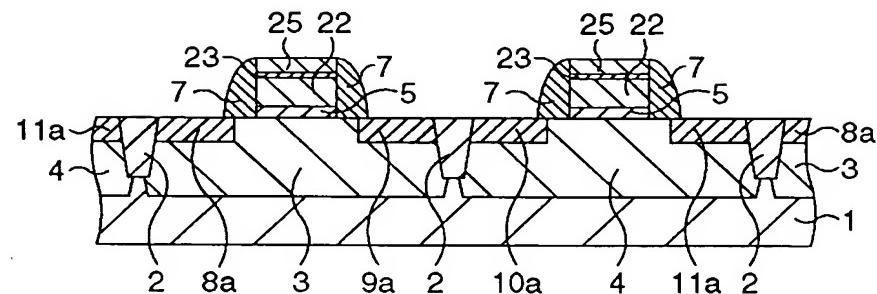


FIG. 7B

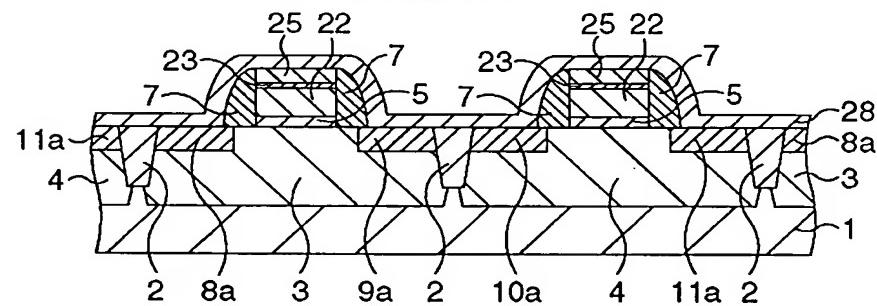


FIG. 7C

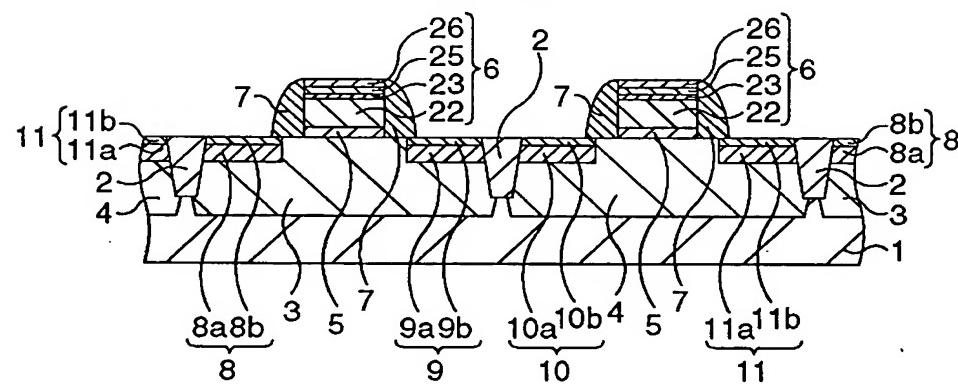


FIG. 7D

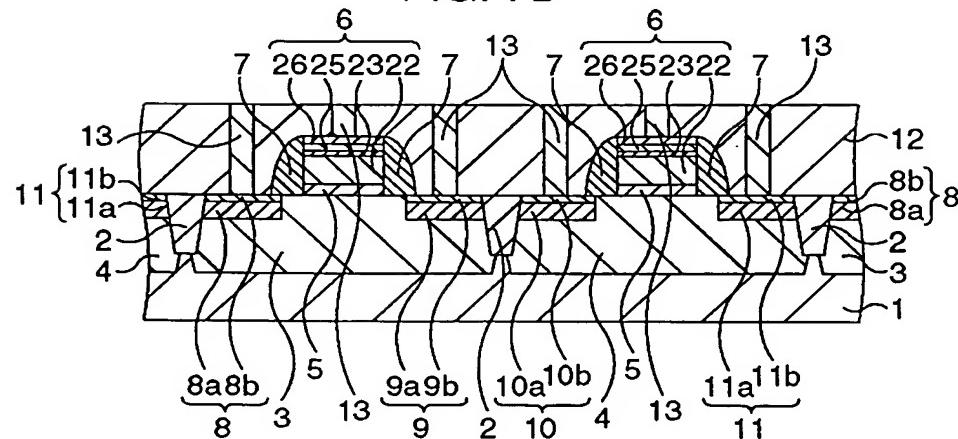


FIG. 8A

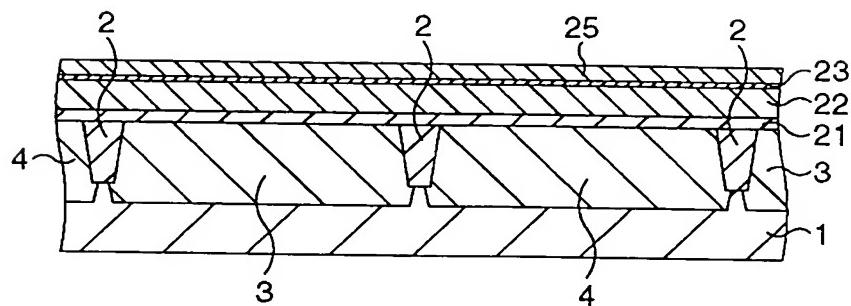


FIG. 8B

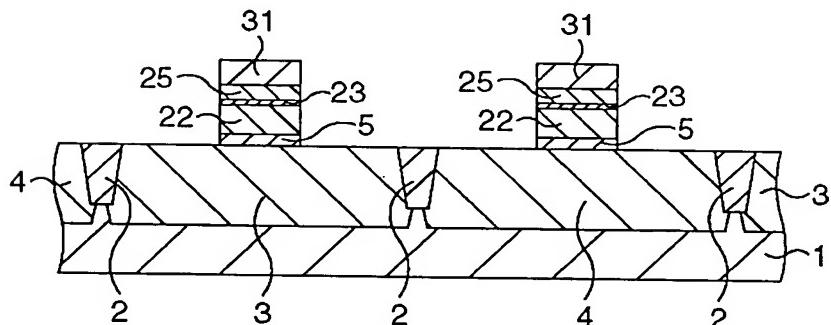


FIG. 8C

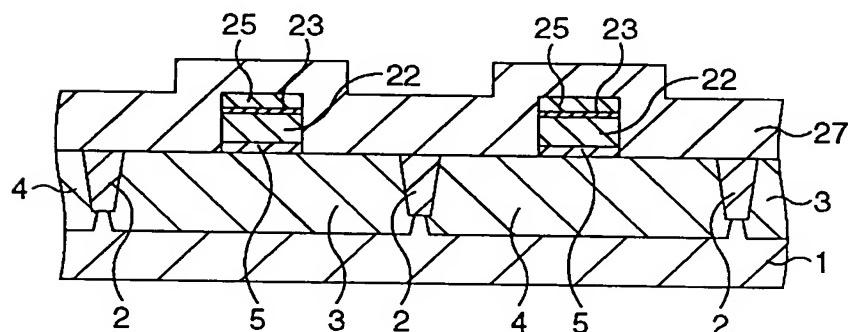


FIG. 8D

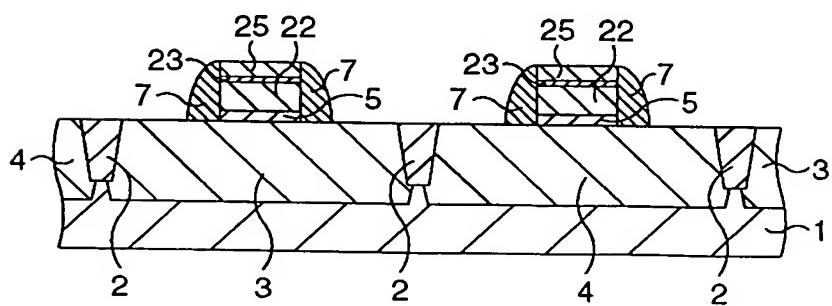


FIG. 9A

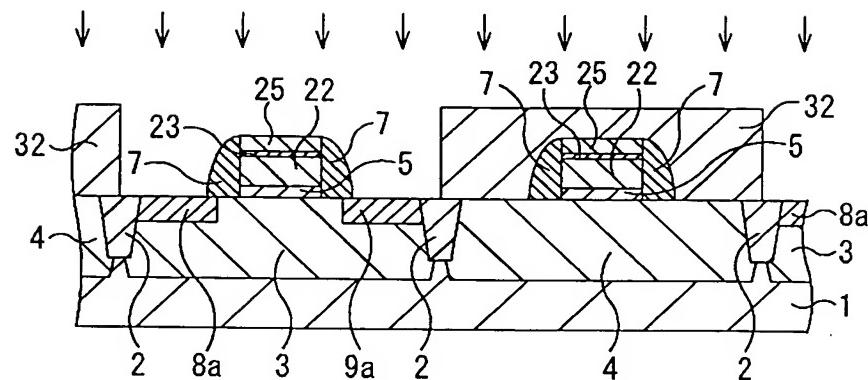


FIG. 9B

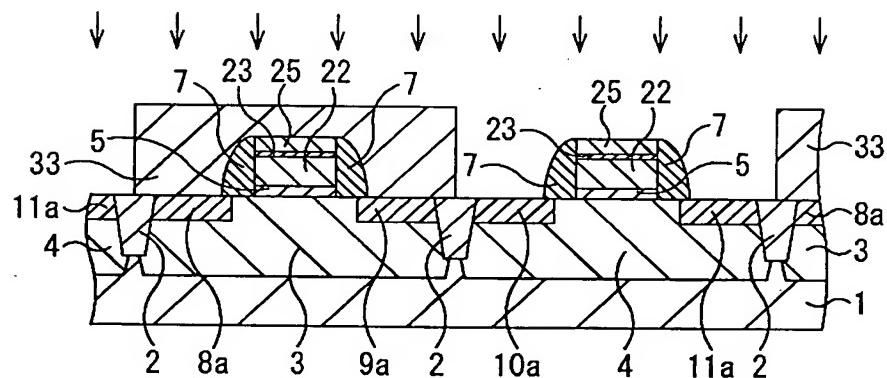


FIG. 9C

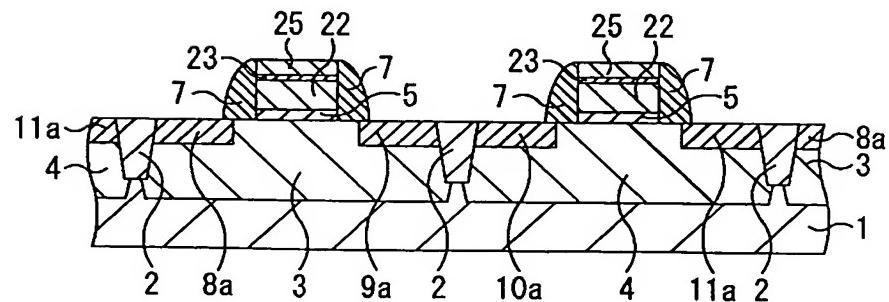
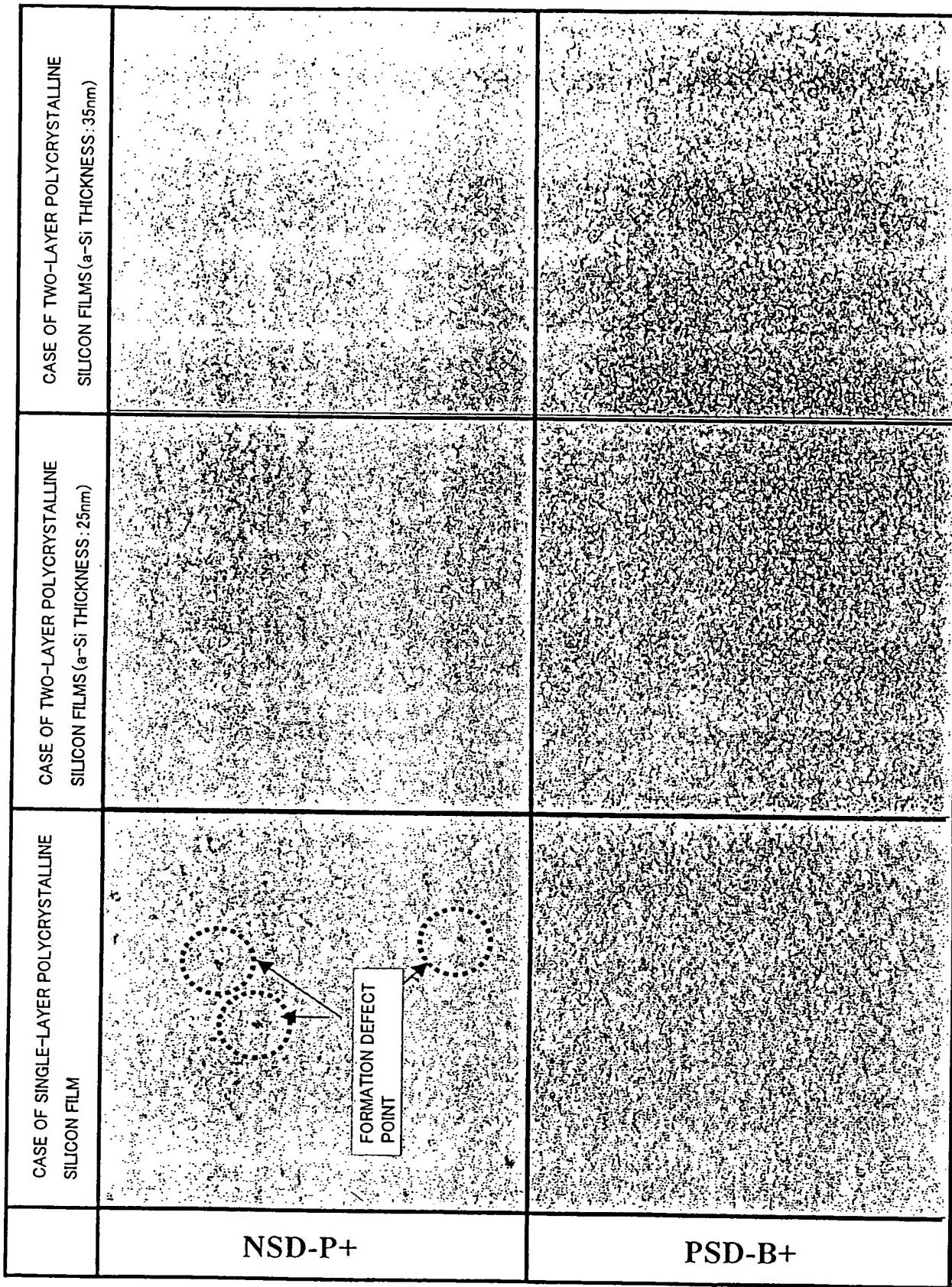
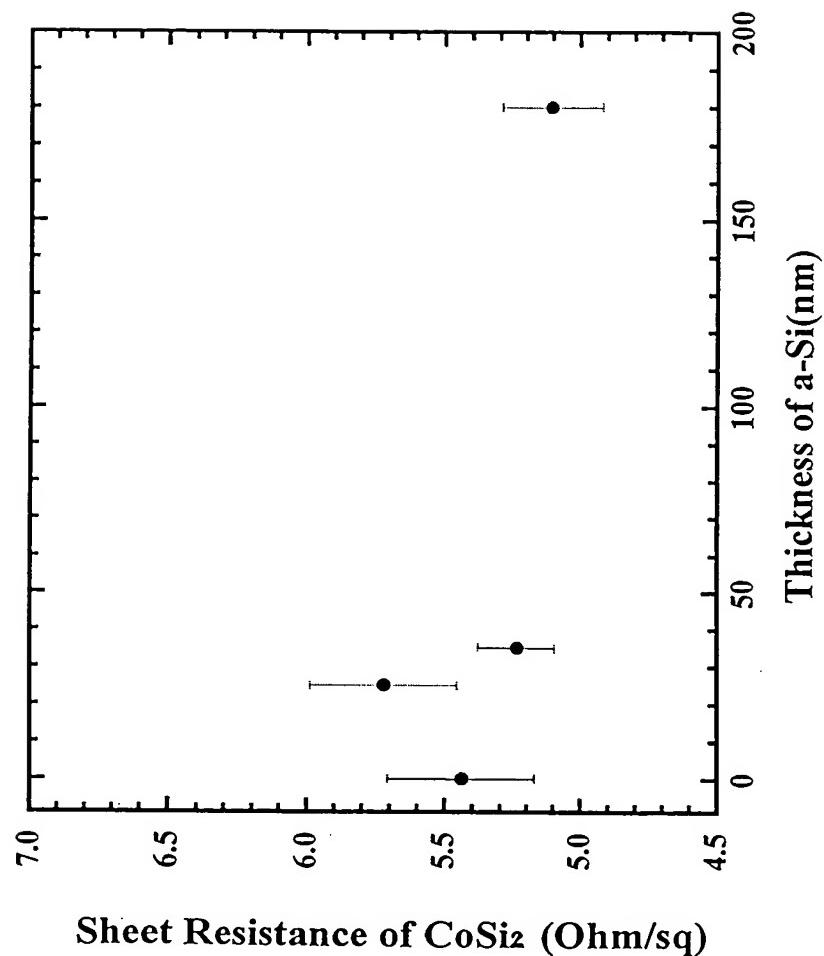


FIG. 10



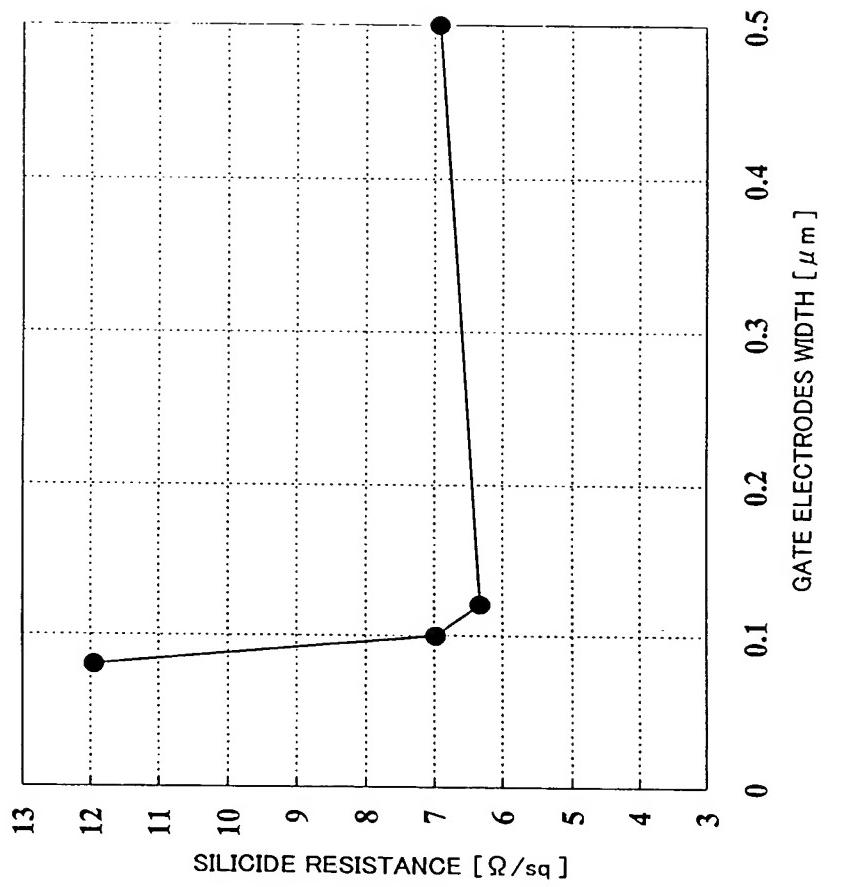
< SURFACE PHOTOGRAPH OF SILICIDE ON TWO-LAYER GATE ELECTRODE STRUCTURE >

FIG. 11



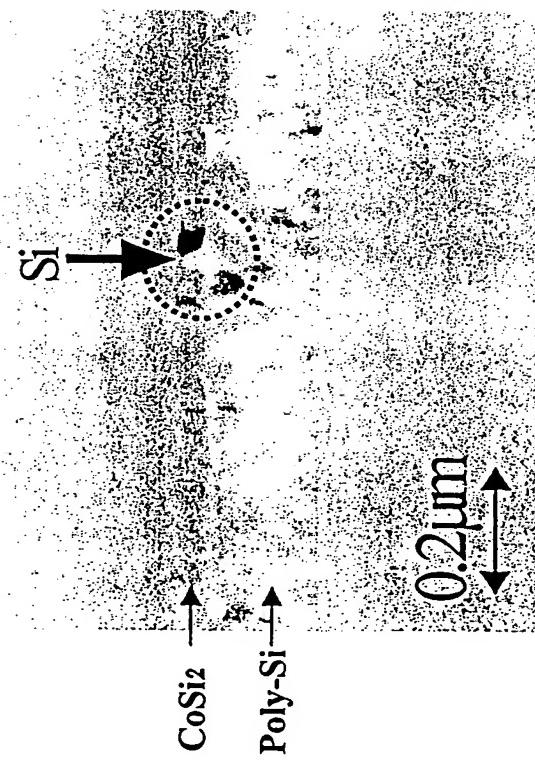
<DEPENDENCE OF SILICIDE RESISTANCE ON FILM THICKNESS OF AMORPHOUS SILICON FILM>

FIG. 12



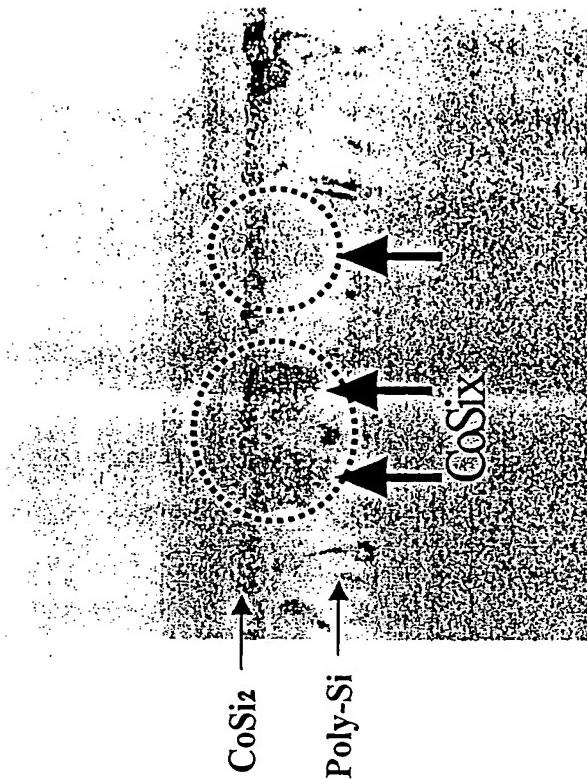
<DEPENDENCE OF COBALT SILICIDE RESISTANCE ON WIDTH OF WIRE>

FIG. 13



<PHOTOGRAPH OF CROSS SECTION OF CoSi₂
FORMATION DEFECT POINT>

FIG. 14



<OVER SILICIDATION REACTION POINT EXAMINED IN
PHOTOGRAPH OF CROSS SECTION>